

<u>NEWS 1</u>	Web Page URLs for STN Seminar Schedule - N. America	
<u>NEWS 2</u>	"Ask CAS" for self-help around the clock	
<u>NEWS 3</u>	SEP 09	CA/CAplus records now contain indexing from 1907 to the present
<u>NEWS 4</u>	AUG 05	New pricing for EUROPATFULL and PCTFULL effective August 1, 2003
<u>NEWS 5</u>	AUG 13	Field Availability (/FA) field enhanced in BEILSTEIN
<u>NEWS 6</u>	AUG 18	Data available for download as a PDF in RDISCLOSURE
<u>NEWS 7</u>	AUG 18	Simultaneous left and right truncation added to PASCAL
<u>NEWS 8</u>	AUG 18	FROSTI and KOSMET enhanced with Simultaneous Left and Right Truncation
<u>NEWS 9</u>	AUG 18	Simultaneous left and right truncation added to ANABSTR
<u>NEWS 10</u>	SEP 22	DIPPR file reloaded
<u>NEWS 11</u>	SEP 25	INPADOC: Legal Status data to be reloaded
<u>NEWS 12</u>	SEP 29	DISSABS now available on STN
<u>NEWS 13</u>	OCT 10	PCTFULL: Two new display fields added
<u>NEWS EXPRESS</u>	OCTOBER 01 CURRENT WINDOWS VERSION IS V6.01a, CURRENT MACINTOSH VERSION IS V6.0b(ENG) AND V6.0Jb(JP), AND CURRENT DISCOVER FILE IS DATED 23 SEPTEMBER 2003	
<u>NEWS HOURS</u>	STN Operating Hours Plus Help Desk Availability	
<u>NEWS INTERNET</u>	General Internet Information	
<u>NEWS LOGIN</u>	Welcome Banner and News Items	
<u>NEWS PHONE</u>	Direct Dial and Telecommunication Network Access to STN	
<u>NEWS WWW</u>	CAS World Wide Web Site (general information)	

Enter NEWS followed by the item number or name to see news on that specific topic.

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FILE 'HOME' ENTERED AT 06:47:29 ON 13 OCT 2003

FILE 'INSPEC' ENTERED AT 06:47:39 ON 13 OCT 2003  
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FILE LAST UPDATED: 13 OCT 2003 <20031013/UP>  
FILE COVERS 1969 TO DATE.

<<< SIMULTANEOUS LEFT AND RIGHT TRUNCATION AVAILABLE IN  
THE BASIC INDEX >>>

```
=> a phase shift mask
    713679 PHASE
    147036 SHIFT
    21527 MASK
L1      516 PHASE SHIFT MASK
          (PHASE (W) SHIFT (W) MASK)
```

=> a exposure optical system  
61904 EXPOSURE

668960 OPTICAL  
1595550 SYSTEM  
L2 1 EXPOSURE OPTICAL SYSTEM  
(EXPOSURE (W) OPTICAL (W) SYSTEM)

=> d 12

L2 ANSWER 1 OF 1 INSPEC (C) 2003 IEE on STN

**Full Text**

AN 2001:6804707 INSPEC DN B2001-02-2550G-151  
TI Influence of electron density distribution at the electron source in a  
projection exposure system.  
AU Kotera, M.; Sakai, M. (Osaka Inst. of Technol., Japan); Shimizu, I.; Tomo,  
Y.; Yoshida, A.; Kojima, Y.; Yamabe, M.  
SO Digest of Papers Micropocesses and Nanotechnology 2000. 2000  
International Micropocesses and Nanotechnology Conference (IEEE Cat.  
No.00EX387)  
Tokyo, Japan: Japan Soc. Appl. Phys, 2000. p.140-1 of xxviii+306 pp. 0  
refs.  
Conference: Tokyo, Japan, 11-13 July 2000  
Sponsor(s): Japan Soc. Appl. Phys.; IEEE Electron Device Soc.; American  
Vacuum Soc.; Assoc. Super-Adv. Electron. Technol.; IEE of Japan; IEICE;  
Japanese Soc. Synchrotron Radiation Res.; Japanese Soc. Electron  
Microscopy; Surface Sci. Soc. Japan; Vacuum Soc. Japan  
ISBN: 4-89114-004-6  
DT Conference Article  
TC Theoretical  
CY Japan  
LA English

=> s excavation

L3 871 EXCAVATION

=> s L1 and L2

L4 0 L1 AND L2

=> s L1 and L3

L5 0 L1 AND L3

=> s resist pattern

12602 RESIST

182954 PATTERN

L6 424 RESIST PATTERN  
(RESIST (W) PATTERN)

=> s L1 and L6

L7 7 L1 AND L6

=> d 17 1-7

L7 ANSWER 1 OF 7 INSPEC (C) 2003 IEE on STN

**Full Text**

AN 2003:7717431 INSPEC DN B2003-10-2550G-142  
TI Preliminary study of 65 nm node alternating **phase-shift mask** fabrication.  
AU Hosono, K.; Ishiwata, N.; Asai, S.; Maruyama, H.; Miyahara, Y. (Fujitsu  
Ltd., Tokyo, Japan); Sanki, S.; Yamashita, Y.; Hotta, Y.; Furukawa, T.;  
Naitou, M.; Miyashita, H.; Noguchi, S.  
SO Proceedings of the SPIE - The International Society for Optical  
Engineering (2002) vol.4889, p.1273-80. 3 refs.  
Published by: SPIE-Int. Soc. Opt. Eng  
Price: CCCC 0277-786X/02/\$15.00

CODEN: PSISDG ISSN: 0277-786X  
SICI: 0277-786X(2002)4889L.1273:PSNA;1-Y  
Conference: 22nd Annual BACUS Symposium on Photomask Technology. Monterey, CA, USA, 1-4 Oct 2002

Sponsor(s): SPIE  
DT Conference Article; Journal  
TC Experimental  
CY United States  
LA English

L7 ANSWER 2 OF 7 INSPEC (C) 2003 IEE on STN

Full   
Text 

AN 1998:5803277 INSPEC DN B9802-2550G-201  
TI Optical proximity correction of alternating phase-shift masks for 0.18 mu m KrF lithography.  
AU Yasuzato, T.; Ishida, S. (VLSI Device Dev. Lab., NEC Corp., Sagamihara, Japan); Shioiri, S.; Tanabe, H.; Kasama, K.  
SO Proceedings of the SPIE - The International Society for Optical Engineering (1997) vol.3051, p.751-62. 5 refs.  
Published by: SPIE-Int. Soc. Opt. Eng  
Price: CCCC 0277-786X/97/\$10.00  
CODEN: PSISDG ISSN: 0277-786X  
SICI: 0277-786X(1997)3051L.751:OPCA;1-O  
Conference: Optical Microlithography X. Santa Clara, CA, USA, 12-14 March 1997  
Sponsor(s): SPIE  
DT Conference Article; Journal  
TC Experimental  
CY United States  
LA English

L7 ANSWER 3 OF 7 INSPEC (C) 2003 IEE on STN

Full   
Text 

AN 1997:5611672 INSPEC DN B9708-2550G-008  
TI Impact of lens aberrations on optical lithography.  
AU Brunner, T.A. (Microelectron. Div., IBM Corp., East Fishkill, NY, USA)  
SO IBM Journal of Research and Development (Jan.-March 1997) vol.41, no.1-2, p.57-67. 18 refs.  
Published by: IBM  
Price: CCCC 0018-8646/97/\$5.00  
CODEN: IBMJAE ISSN: 0018-8646  
SICI: 0018-8646(199701/03)41:1/2L.57:ILAO;1-N  
DT Journal  
TC Theoretical  
CY United States  
LA English

L7 ANSWER 4 OF 7 INSPEC (C) 2003 IEE on STN

Full   
Text 

AN 1996:5426662 INSPEC DN B9701-2550G-005; C9701-7410D-002  
TI Improvement of **resist pattern** fidelity with partial attenuated **phase shift mask**.  
AU Yasuzato, T.; Ishida, S.; Kasama, K. (VLSI Dev. Div., NEC Corp., Sagamihara, Japan)  
SO Proceedings of the SPIE - The International Society for Optical Engineering (1996) vol.2726, p.496-507. 12 refs.  
Published by: SPIE-Int. Soc. Opt. Eng  
Price: CCCC 0 8194 2102 2/96/\$6.00  
CODEN: PSISDG ISSN: 0277-786X  
SICI: 0277-786X(1996)2726L.496:IRPF;1-Q  
Conference: Optical Microlithography IX. Santa Clara, CA, USA, 13-15 March

1996

Sponsor(s): SPIE

DT Conference Article; Journal

TC Practical; Theoretical; Experimental

CY United States

LA English

L7 ANSWER 5 OF 7 INSPEC (C) 2003 IEE on STN

**Full**

Text

AN 1995:5082029 INSPEC DN B9512-2550G-016

TI A study of optical proximity effects using off-axis illumination with attenuated **phase shift mask**.

AU Ahn, C.-N.; Baik, K.-H.; Lee, Y.-S.; Kim, H.-E.; Hur, I.-B.; Kim, Y.-S.; Kim, J.-H.; Choi, S.-H. (Semicond. R. &amp; D. Labs., Hyundai Electron. Ind. Co. Ltd., Kyungki-do, South Korea)

SO Proceedings of the SPIE - The International Society for Optical Engineering (1995) vol.2440, p.222-39. 7 refs.

Price: CCCC 0 8194 1788 2/95/\$6.00

CODEN: PSISDG ISSN: 0277-786X

Conference: Optical/Laser Microlithography VII. Santa Clara, CA, USA, 22-24 Feb 1995

Sponsor(s): SPIE

DT Conference Article; Journal

TC Practical; Theoretical; Experimental

CY United States

LA English

L7 ANSWER 6 OF 7 INSPEC (C) 2003 IEE on STN

**Full**

Text

AN 1995:4968479 INSPEC DN B9507-2550G-035

TI Poly(cyclohexyl 2-cyanoacrylate-co-ethoxyethyl 2-cyanoacrylate) as a positive tone electron beam resist for **phase-shift mask** fabrication.

AU Tamura, A.; Yonezawa, M. (Electron. Res. Lab., Toppan Printing Co. Ltd., Saitama, Japan); Sato, M.; Okuyama, T.

SO Proceedings of the SPIE - The International Society for Optical Engineering (1994) vol.2254, p.228-36. 4 refs.

Price: CCCC 0 8194 1563 4/94/\$6.00

CODEN: PSISDG ISSN: 0277-786X

Conference: Photomask and X-Ray Mask Technology. Kanagawa, Japan, 22 April 1994

Sponsor(s): SPIE; BACUS

DT Conference Article; Journal

TC Practical; Experimental

CY United States

LA English

L7 ANSWER 7 OF 7 INSPEC (C) 2003 IEE on STN

**Full**

Text

AN 1992:4311819 INSPEC DN B9302-2550G-046

TI Resolution improvement with annular illumination.

AU Tounai, K.; Tanabe, H.; Nozue, H.; Kasama, K. (VLSI Dev. Div., NEC Corp., Kanagawa, Japan)

SO Proceedings of the SPIE - The International Society for Optical Engineering (1992) vol.1674, pt.2, p.753-64. 5 refs.

Price: CCCC 0 8194 0829 8/92/\$4.00

CODEN: PSISDG ISSN: 0277-786X

Conference: Optical/Laser Microlithography V. San Jose, CA, USA, 11-13 March 1992

Sponsor(s): SPIE

DT Conference Article; Journal

TC Practical; Experimental

CY    United States  
LA    English

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